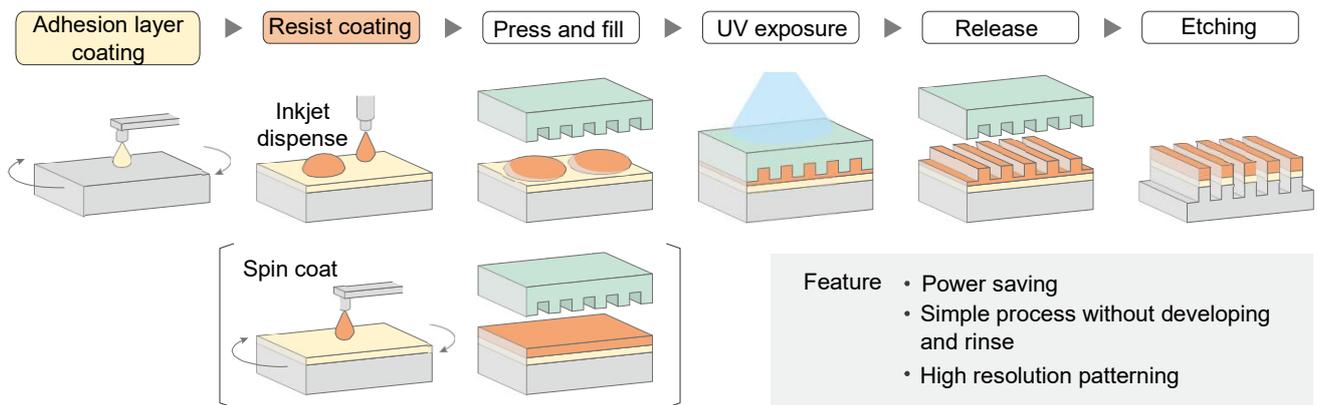


Nanoimprint Lithography (NIL) material

Overview of FUJIFILM technology / product

NIL technology



FUJIFILM NIL material

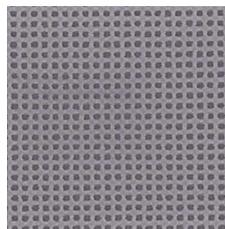
UV curable NIL resist for advanced semiconductor applications

High resolution mask patterns are faithfully transferred. Complex patterns (3D structures, etc.) can be formed in a shot. Contribute to cost reduction and power saving in advanced semiconductor manufacturing.

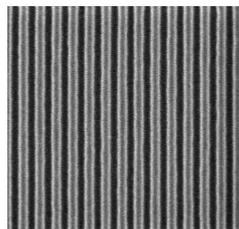
NIL adhesion material

Provide adhesion between substrate and resist to prevent loss of pattern transfer onto the resist when the mask is peeled off at high speed.

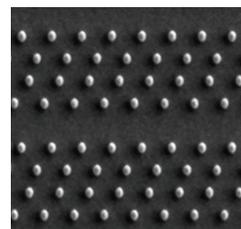
Patterning images



hp 18 nm C/H



hp 19 nm L/S



24 x 40 nm Pillar

Provided by Canon Inc.

Examples of NIL application

